

3rd European Nanofabrication Research Infrastructure Symposium – ENRIS 2023

15-17.5 2023, Paris-Saclay - France

Call for Papers

We are very honored to invite you to contribute and participate to the **3**rd **European Nanofabrication Research Infrastructure Symposium – ENRIS 2023**, a conference on cleanroom operation, management and user training, jointly organized by the **C2N**, **EuroNanoLab** and **RENATECH**

The conference will take place at **UNIVERSITE PARIS-SACLAY** from **15 to 17 May 2023**. More information available at: <u>http://euronanolab.eu/enris-2023/</u>

Presentations within the following thematic areas are expected, but any other relevant suggestion is strongly encouraged:

- New Processes development
- Technologies for emerging scientific fields
- Metrological characterization
- Web interfaces to manage cleanrooms
- Open Science and Open Access
- Data management for nanofabrication
- Energy savings / costs / supply chains issues / sustainability
- Health and safety issues & waste management
- Research Infrastructures Development and Valorisation / interface between FabLabs and micro-nano-fabrication facilities
- Fostering technology transfer and innovation: experiences and lessons learned
- Legal aspects of procurements and intellectual properties rights management
- Training
- Other suggestions

Overall visions, running experiences, work-in-progress, challenges to be faced, with the aim of sharing experiences and stimulate discussion or collaborations on micro- and nano-technologies for cleanroom operation, management and user training are very welcome.

Abstract submission

Abstracts of your contributions shall be made in writing to <u>info@euronanolab.eu</u> stating « ENRIS 2023 – abstract submission » in the subject, by **March 15th 2023.**

Important Dates

Abstract submission opening: Abstract submission deadline: Notification of acceptance: Final program publication: February 15th 2023 March 15th 2023 April 1 - 15th 2023 April 15th 2023

Contact: info@euronanolab.eu